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	First Named Inventor	Sakai	
	An Unit	1752	
	Examiner Name	Shi J. Lo	
Total Number of Pages in This Submission	3	Attorney Docket Number	Toyo-3

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Firm Name	Gomez International Patent Office		
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**PATENT APPLICATION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN THE APPLICATION OF
Nobuji Sakai, et al.

DOCKET NO.: Toyo-3

SERIAL NO.: 10/526,383

EXAMINER: Sin J. Lee

FILED: September 13, 2005

ART UNIT: 1752

CONFIRMATION NO.: 3829

**TITLE: Radiation-Sensitive Negative-Type Resist Composition for Pattern
Formation and Pattern Formation Method**

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REQUEST FOR CORRECTED FILING RECEIPT AND REPUBLICATION

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Sir:

The Applicants request that the Filing Receipt in the above-identified application be corrected as follows:

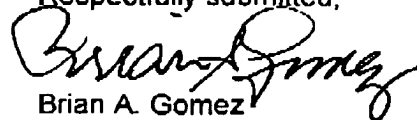
From: Foreign Applications
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A copy of the corresponding PCT publication is attached as evidence.

Applicant requests that the correction be effected prior to the projected publication date of 03 August 2006.

Respectfully submitted,



Brian A. Gomez
Attorney for Applicants
Registration No. 44,718
Gomez International Patent Office
1501 N. Rodney Street, Suite 101
Wilmington, DE 19806
Telephone: (302) 351-3323
Facsimile: (302) 351-8456
Email: bgomez@gomez-ipo.com

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(71) Applicant (for all designated States except US): TOYO GOSSEI CO., LTD. [JP/JP]; 1603, Kaminimiyoden, Ichikawa-shi, Chiba 272-0012 (JP).

(72) Inventors; and

(75) Inventors/Applicants (for US only): SAKAI, Nobuji [JP/JP]; c/o Photosensitive Materials Research Center,

TOYO GOSSEI CO., LTD., 2-1, Wakahagi 4-chome, Inba-mura, Inba-gun, Chiba 270 1609 (JP). TADA, Kentaro [JP/JP]; c/o Photosensitive Materials Research Center, TOYO GOSSEI CO., LTD., 2-1, Wakahagi 4-chome, Inba-mura, Inba-gun, Chiba 270-1609 (JP).

(74) Agent: KURIHARA, Hiroyuki; Kurihara International Patent Office, Iwasaki Bldg.7F, 3-15 Hiruo 1 chome, Shihuya ku, Tokyo 150-0012 (JP).

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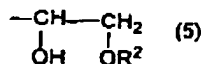
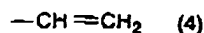
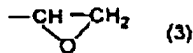
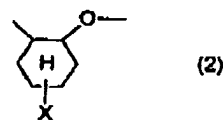
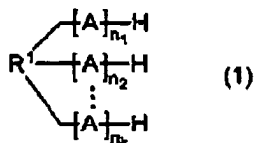
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(54) Title: RADIATION-SENSITIVE NEGATIVE-TYPE RESIST COMPOSITION FOR PATTERN FORMATION AND PATTERN FORMATION METHOD



(57) Abstract: The radiation sensitive negative-type resist composition for pattern formation containing an epoxy resin, a radiation-sensitive cationic polymerization initiator, and a solvent for dissolving the epoxy resin therein, characterized in that the resist composition, through drying, forms a resist film having a softening point falling within a range of 30 to 120 °C and that the epoxy resin is represented by formula (1): (wherein R¹ represents a moiety derived from an organic compound having k active hydrogen atoms (k represents an integer of 1 to 100); each of n₁, n₂, through n_k represents 0 or an integer of 1 to 100; the sum of n₁, n₂, through n_k falls within a range of 1 to 100; and each of "A"s, which may be identical to or different from each other, represents an oxy-cyclohexane skeleton represented by formula (2): (wherein X represents any of groups represented by formulas (3) to (5); and at least two groups represented by formula (3) are contained in one molecule of the epoxy resin)).

WO 2004/023213 A1